



LYNRED Advanced Developments in the Field of Infra Red Imaging technology

Patrick Abraham Strategy, communication and Technology Department LYNRED, France patrick.abraham@lynred.com

September 14-18, 2020











□ LYNRED presentation

Very Large dimension, Very high performance IR sensors for Science and Space Applications

□ Micro-bolometer sensors for thermal sensing











LYNRED





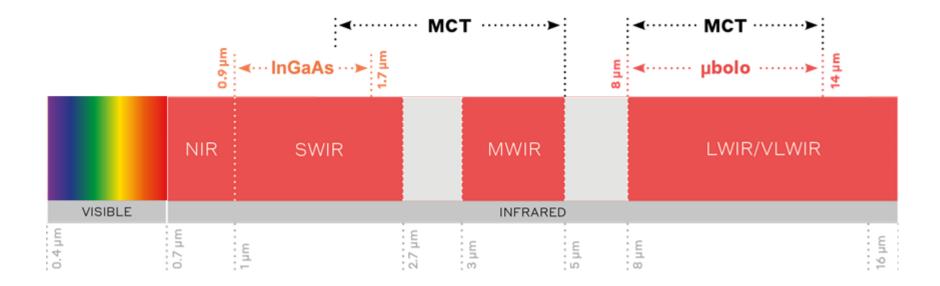








- □ SOFRADIR and ULIS merged to become LYNRED
- □ #2 worldwide IR detector manufacturer offering the largest product portfolio



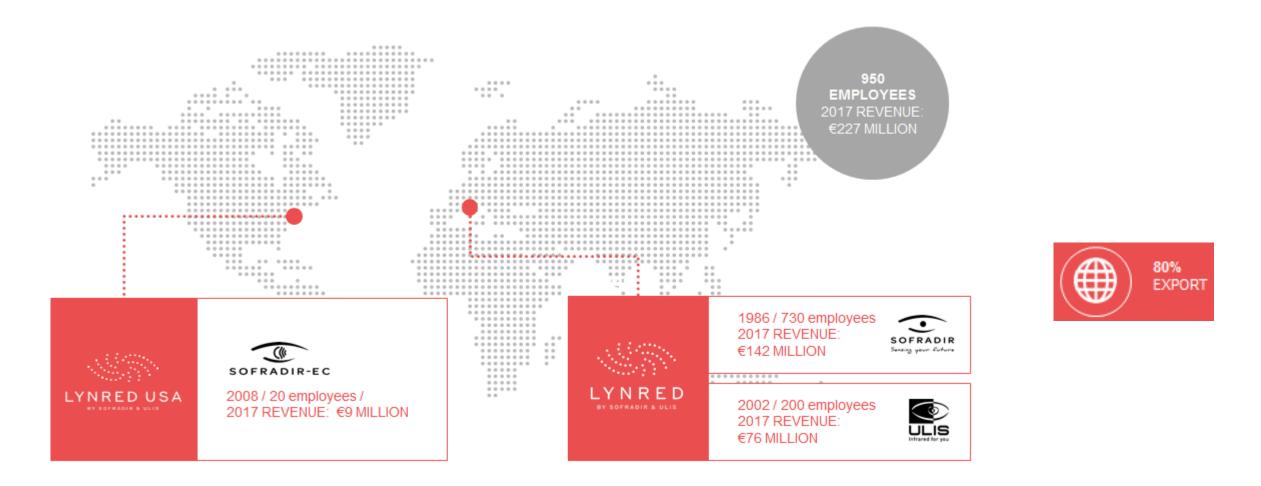






We Are



















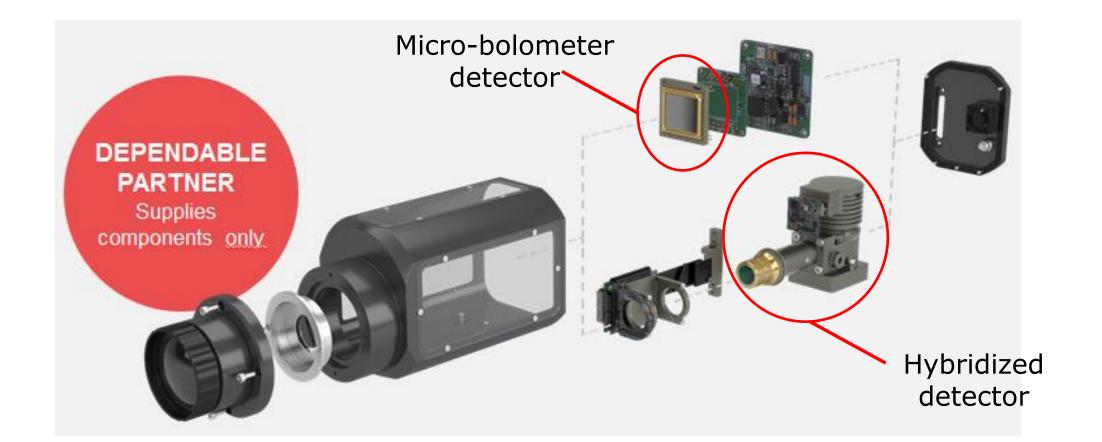














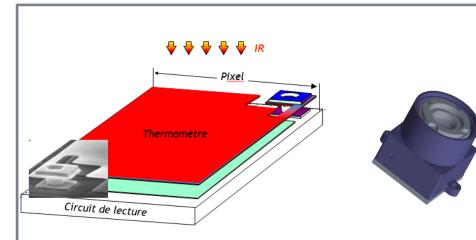






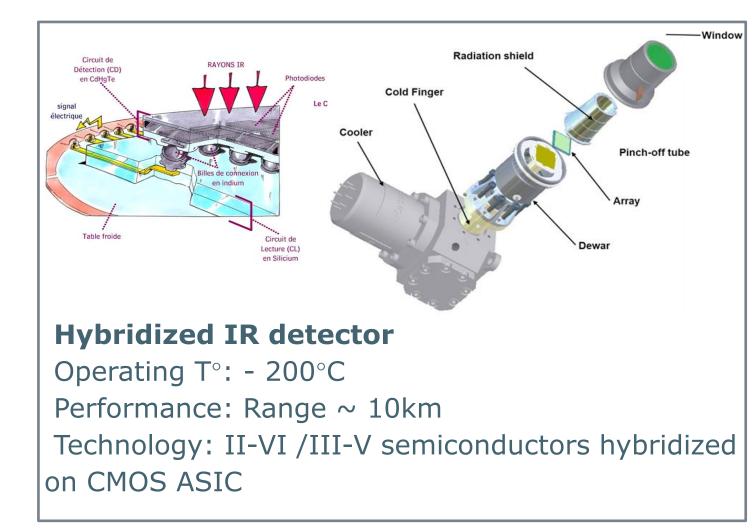
We Do





Micro-bolometer IR detector

Operating T[°]: Room T[°] Performance: Range ~ 1km Technology: MEMs above IC











We Serve













Very Large dimension Very high performance IR sensors for Science and Space Applications







2K² FPA for EELT new generation of telescope





Earth observation and Science (astronomy...) need very large dimension and high performance Focal Plane Array



European Extremely Large Telescope (EELT)

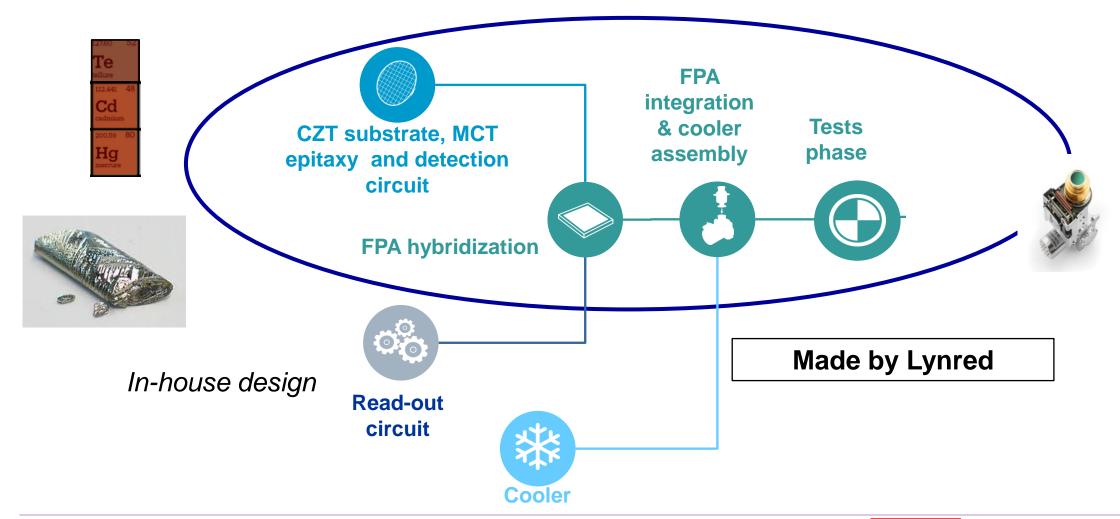






Vertical Industrial Model for II-VI Technology









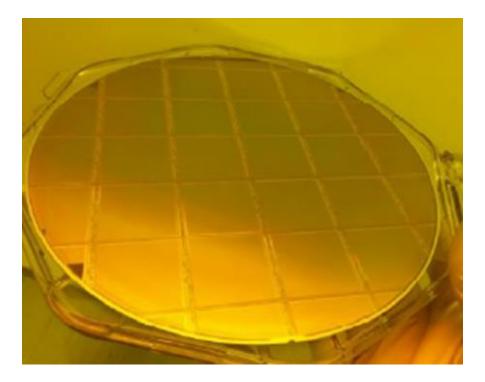




ROIC CMOS Technology



13



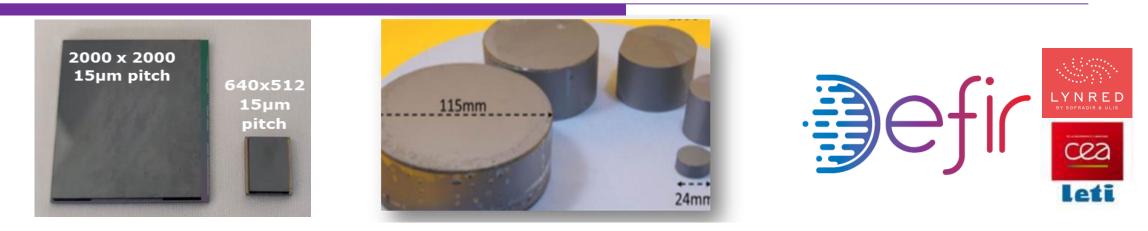
- Very large components with ROIC dimensions larger than 200 mm CMOS maximum reticule size
- Development of specific stitching process for LYNRED
- Development of CMOS wafer post process for hybridization of very large components





Increase CZT Substrate Size





□ CZT wafer manufacturing and MCT epitaxy:

5x5cm² CZT : industrial standard for the production of 640x512 MWIR Scorpio FPAs.

□ Increase of CZT wafer size up to 4" In-house CZT bulk manufacturing and epitaxy:

- On-going developments for CZT ingot diameter > 4.5".
- Increase of CZT ingot diameter from 0.9" (late 70's) to 4.5" (today).







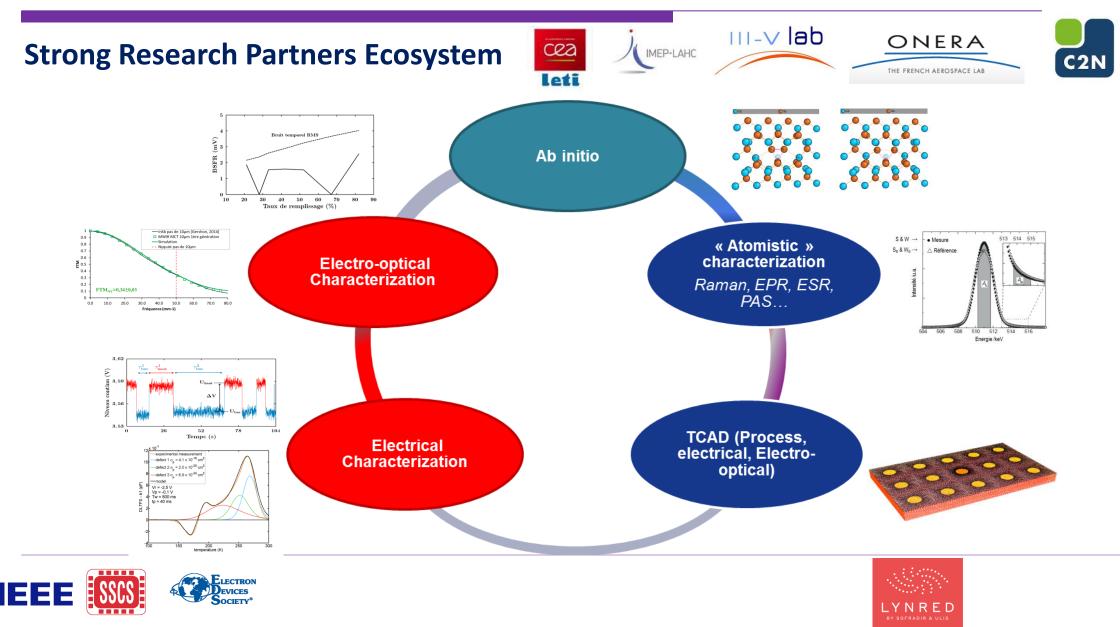


LYNRED R&D Approach



...

110





Increase Substrate Quality And Affordability



- □ CZT bulk process improvements:
 - Increase of single crystal yield.
- □ Better CZT material quality:
 - Suppression of Te-rich and Cd-rich 2nd phase defects.
 - Dislocation density reduction from mid-to-high 10⁴ to low 10³ cm⁻².











P on N Technology Performances



Very low photon flux in Scientific and Space observations.

Dark current has to be as low as possible

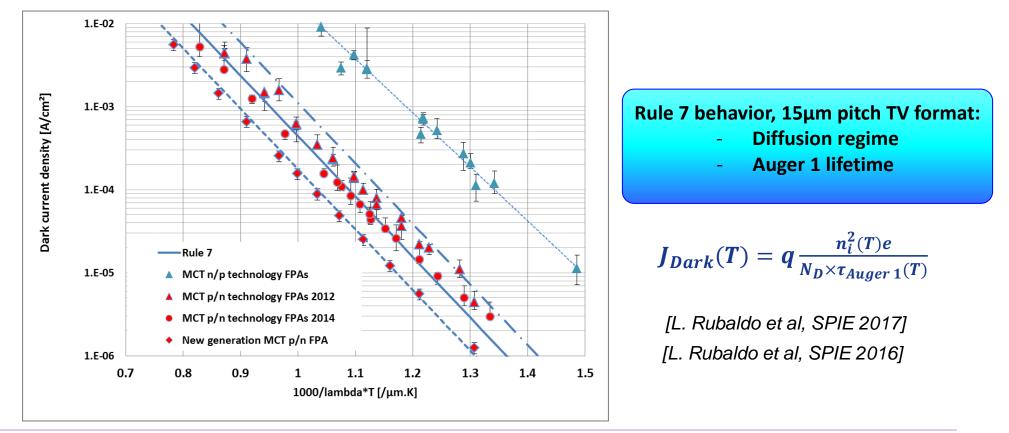








Image Quality Challenges: MTF & MRTD



Minority carrier lifetime increase to decrease J_{dark}

$$\tau \nearrow \text{ for Jdark } \supseteq \Longrightarrow \text{Ldiff } \checkmark L_{diff} = \sqrt{\frac{kT}{q} \mu \times \tau}$$

➔ Diffusion length increase

But.... Diffusion length increase decreases MTF (↑cross talk) and degrades MRTD

$$MRTD = \frac{\sqrt{K_1 \times NETD^2 + K_2 \times RFPN^2}}{MTF}$$

K1 and K2: system dependent constants MRTD: Minimum Resolvable Temperature Difference NETD: Noise Equivalent Temperature Difference MTF: Modulation Transfer Function RFPN: Residual Fixe Pattern Noise Design optimization to ...

• Maximize MTF

Maximize QE

 Minimize Noise: temporal, spatial for ROIC and photodetector

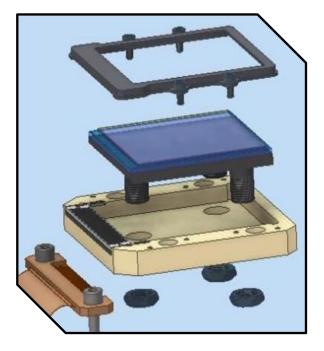






Project achievement







Selected for SVOM mission (Gamma emission study 2020-2026)









Micro-bolometer sensors for thermal sensing









Micro-bolometer development motivations



Today's Technological development in uncooled IR detectors

 \succ Pixel size reduction : below 12 μm ... ? μm

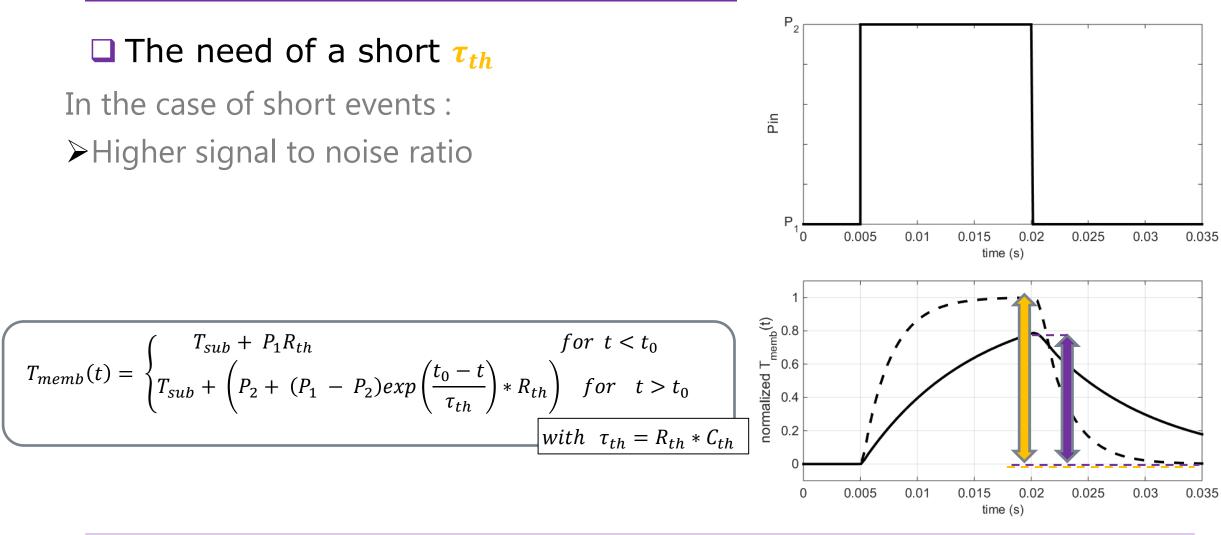
System integration as close as possible to detector development

> Improve FOM beyond NETD



Value addition





BOLOMETER THERMAL TIME CONSTANT

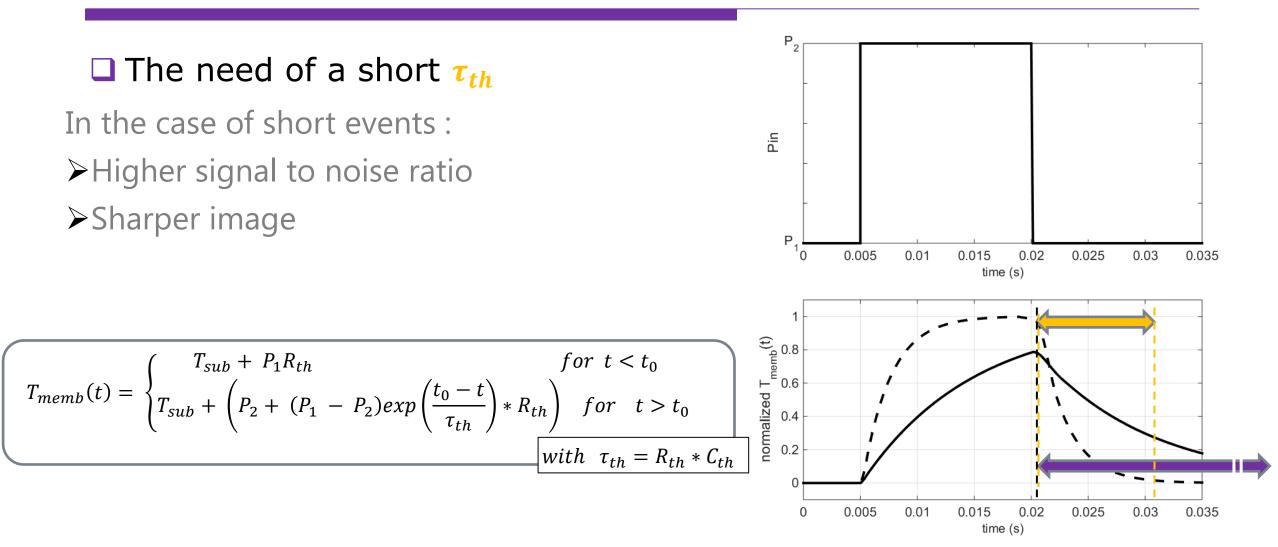


on Microelectronics









BOLOMETER THERMAL TIME CONSTANT



on Microelectronics









BOLOMETER THERMAL TIME CONSTANT





Higher signal to noise ratioSharper image























People at LYNRED who made all this happen!

Alexandre Kerlain, Diane Sam-Giao, Vincent Destefanis, Pascal Leboterf, Julien Roumegoux, Laurent Rubaldo, Nicolas Boudou, Alain Durand...

This work is funded by the French Public Authorities, under the coordination of the French Ministry of Industry, in the frame of the Important Project of Common European Interest (IPCEI) on microelectronics



The IPCEI is also funded by Public Authorities from Germany, Italy and U.K.





